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### **Education**

08.2007 – 04.2011 Dr. rer. nat, *summa cum laude* 

Leibniz Universität Hannover, Germany

Institut für Festkörperphysik (Prof. Herbert Pfnür)

· Adsorption of organic molecules on wide band-gap insulators

07.2005 – 08.2007 Research assistant, Fudan University

Institute of Microelectronic

· High-k dielectrics in nonvolatile memory

09.2002 – 07.2005 MSc. in Electrical Engineering, Fudan University

Institute of Microelectronics

· DFT study on atomic layer deposition of high-k gate dielectrics

09.1998 – 07.2002 BSc., Fudan University, Shanghai, China

## Research Experience

06.2016 – present Post-doctoral researcher, UCLouvain, Belgium

Institute of Condensed Matter and Nanosciences

Profs. Gian-Marco Rignanese and Geoffroy Hautier

· Multicomponent alloys

· Emerging kesterite solar absorbers

· Many-body perturbation theory

· Nonempirical hybrid density functional

· High-throughput computational screening

04.2011 – 03.2016 Post-doctoral researcher, Ecole Polytechnique Fédérale de Lausanne (EPFL)

Chair of Atomic Scale Simulation

Prof. Alfredo Pasquarello

· Defects in semiconductors and insulators

· Interfaces in semiconductor heterojunctions

 $\cdot$  Advanced electronic-structure methods: GW approximation and hybrid functionals

 $\cdot$  Electronic structure of liquid water: many-body and nuclear quantum effects

# **Coding skills**

FORTRAN, C, PYTHON, GNU BASH, MPI.

Active developer for ABINIT and QUANTUM ESPRESSO.

# Code developments

ABINIT Bootstrap exchange-correlation kernel for accurate GW quasiparticle energies,

Gygi-Baldereschi auxiliary function for the treatment of Coulomb singularity

QUANTUM-ESPRESSO Range-separated hybrid density functional

FNV Python class for finite-size-corrections of periodic charged defects

(https://github.com/wayn3/FNV)

# **Teaching Activities**

03.2019 - 06.2019	Masters course: Atomistic and Nanoscopic Simulations
	Teaching assistance, UCLouvain
04.2012 - 04.2016	Masters course: Computational Simulation and Physical Systems I & II
	Teaching assistance, EPFL
06.2013 - 04.2014	Supervising a Masters student (Karim Steiner)
	Project: Band-offset of lattice matched semiconductor heterojunctions

### **Recent Talks and Seminars**

05.2021	MRS Spring Meeting 2021 (virtual)
03.2021	Talk: "Origin of Low Conversion Efficiency of Cu <sub>2</sub> ZnSnS <sub>4</sub> Kesterite Solar Absorber"
09.2018	Swiss Physics Society Annual Meeting 2018, Lausanne, Switzerland
07.2010	Invited talk: "Electronic structures through $GW$ and hybrid functionals"
00 2017	·
08.2017	29th International Conference on Defects in Semiconductors (ICDS), Matsue, Japan
	Invited talk: "Towards accurate determination of defect levels in semiconductors"
05.2017	ABINIT Developer Workshop 2017, Frèjus, France
	Invited talk: "Accurate band gaps via efficient vertex corrections in $GW$ "
10.2015	Université catholique de Louvain, Belgium
	Invited seminar: "Efficient vertex corrections in $GW$ "
09.2015	Psi-к 2015 conference, San Sebastian, Spain
	Talk: "Accurate band gaps via efficient vertex corrections in $GW$ "
07.2015	International Conference on Defects in Semiconductors (ICDS 15), Espoo, Finland
	Talk: "Determination of defect energy levels through $GW$ "
04.2015	"Nothing is Perfect" workshop, Ascona, Switzerland
	Invited Talk: "First-principles determination of defect energy levels through $GW$ "
08.2014	International conference on the physics of semiconductors (ICPS 14), Austin, USA
	Talk: "Band offset of lattice-matched semiconductor heterojunctions"
07.2013	International Conference on Defects in Semiconductors (ICDS 13), Bologna, Italy
	Talk: "Defect energy levels: Hybrid functionals vs GW"
	<b>5</b> , <b>7</b>

## Miscellaneous

Referee for Phys. Rev. Lett., Phys. Rev. B, Appl. Phys. Lett., J. Phys. Chem. Lett., J. Phys. Chem., npj Comput. Mater.

### **Publications in Chronological Order**

- [1] G. Bokas, W. Chen, A. Hilhorst, P. Jacques, S. Gorsse, and G. Hautier, "Unveiling the thermodynamic driving forces for high entropy alloys formation through big data ab initio analysis", Scr. Mater. **202**, 114000 (2021).
- [2] W. Chen, D. Dahliah, G.-M. Rignanese, and G. Hautier, "Origin of the low conversion efficiency in Cu<sub>2</sub>ZnSnS<sub>4</sub> kesterite solar cells: the actual role of cation disorder", Energy Environ. Sci., (2021).
- [3] M. Markov et al., "Ferroelectricity and multiferroicity in anti–Ruddlesden–Popper structures", Proc. Natl. Acad. Sci. 118, e2026020118 (2021).
- [4] A. Tal, W. Chen, and A. Pasquarello, "Vertex function compliant with the Ward identity for quasiparticle self-consistent calculations beyond *GW*", Phys. Rev. B **103**, L161104 (2021).
- [5] X. Gonze et al., "The Abinit project: impact, environment and recent developments", Comput. Phys. Commun. **248**, 107042 (2020).
- [6] T. Bischoff, J. Wiktor, W. Chen, and A. Pasquarello, "Nonempirical hybrid functionals for band gaps of inorganic metal-halide perovskites", Phys. Rev. Materials 3, 123802 (2019).
- [7] W. Chen, J. George, J. B. Varley, G.-M. Rignanese, and G. Hautier, "High-throughput computational discovery of In<sub>2</sub>Mn<sub>2</sub>O<sub>7</sub> as a high Curie temperature ferromagnetic semiconductor for spintronics", npj Comput. Mater. **5**, 72 (2019).
- [8] S. Hadke, W. Chen, J. M. R. Tan, M. Guc, V. Izquierdo-Roca, G.-M. Rignanese, G. Hautier, and L. H. Wong, "Effect of Cd on cation redistribution and order-disorder transition in Cu<sub>2</sub>(Zn, Cd)SnS<sub>4</sub>", J. Mater. Chem. A 7, 26927 (2019).
- [9] L. A. Burton, F. Ricci, W. Chen, G.-M. Rignanese, and G. Hautier, "High-throughput identification of electrides from all known inorganic materials", Chem. Mater. **30**, 7521 (2018).
- [10] W. Chen, G. Miceli, G.-M. Rignanese, and A. Pasquarello, "Nonempirical dielectric-dependent hybrid functional with range separation for semiconductors and insulators", Phys. Rev. Materials 2, 073803 (2018).
- [11] W. Chen and A. Pasquarello, "Comment on 'Fundamental resolution of difficulties in the theory of charged point defects in semiconductors", Phys. Rev. Lett. **120**, 039603 (2018).
- [12] Z. Guo, F. Ambrosio, W. Chen, P. Gono, and A. Pasquarello, "Alignment of redox levels at semiconductor–water interfaces", Chem. Mater. **30**, 94 (2018).
- [13] G. Miceli, W. Chen, I. Reshetnyak, and A. Pasquarello, "Nonempirical hybrid functionals for band gaps and polaronic distortions in solids", Phys. Rev. B **97**, 121112(R) (2018).
- [14] W. Chen and A. Pasquarello, "Accuracy of GW for calculating defect energy levels in solids", Phys. Rev. B **96**, 020101(R) (2017).
- [15] A. Faghaninia et al., "A computational assessment of the electronic, thermoelectric, and defect properties of bournonite (CuPbSbS3) and related substitutions", Phys. Chem. Chem. Phys. 19, 6743 (2017).
- [16] W. Chen, F. Ambrosio, G. Miceli, and A. Pasquarello, "*Ab initio* electronic structure of liquid water", Phys. Rev. Lett. **117**, 186401 (2016).
- [17] W. Chen and A. Pasquarello, "Accurate band gaps of extended systems via efficient vertex corrections in GW", Phys. Rev. B **92**, 041115(R) (2015).
- [18] W. Chen and A. Pasquarello, "First-principles determination of defect energy levels through hybrid density functionals and *GW*", J. Phys.: Condens. Matter **27**, 133202 (2015).
- [19] W. Chen and A. Pasquarello, "Band-edge positions in GW: Effects of starting point and self-consistency", Phys. Rev. B **90**, 165133 (2014).
- [20] K. Steiner, W. Chen, and A. Pasquarello, "Band offsets of lattice-matched semiconductor heterojunctions through hybrid functionals and G<sub>0</sub>W<sub>0</sub>", Phys. Rev. B **89**, 205309 (2014).

- [21] W. Chen and A. Pasquarello, "Correspondence of defect energy levels in hybrid density functional theory and many-body perturbation theory", Phys. Rev. B 88, 115104 (2013).
- [22] W. Chen and A. Pasquarello, "Band-edge levels in semiconductors and insulators: Hybrid density functional theory versus many-body perturbation theory", Phys. Rev. B **86**, 035134 (2012).
- [23] W. Chen, C. Tegenkamp, H. Pfnür, and T. Bredow, "Anomalous molecular orbital variation upon adsorption on a wide band gap insulator", J. Chem. Phys. **132**, 214706 (2010).
- [24] W. Chen, C. Tegenkamp, H. Pfnür, and T. Bredow, "Color centers in NaCl by hybrid functionals", Phys. Rev. B 82, 104106 (2010).
- [25] W. Chen, C. Tegenkamp, H. Pfnür, and T. Bredow, "Insight from first-principles calculations into the interactions between hydroxybenzoic acids and alkali chloride surfaces", J. Phys. Chem. C 114, 460 (2010).
- [26] W. Chen, C. Tegenkamp, H. Pfnür, and T. Bredow, "Tailoring band gaps of insulators by adsorption at surface defects: Benzoic acids on NaCl surfaces", Phys. Rev. B **79**, 235419 (2009).
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- [28] M. Zhang, W. Chen, S.-J. Ding, Z.-Y. Liu, Y. Huang, Z.-W. Liao, and D. W. Zhang, "Physical and electrical characterization of atomic-layer-deposited Ru nanocrystals embedded into Al2O3 for memory applications", J. Phys. D: Appl. Phys. 41, 032007 (2008).
- [29] W. Chen, W.-J. Liu, M. Zhang, S.-J. Ding, D. W. Zhang, and M.-F. Li, "Multistacked Al<sub>2</sub>O<sub>3</sub>-HfO<sub>2</sub>-SiO<sub>2</sub> tunnel layer for high-density nonvolatile memory application", Appl. Phys. Lett. **91**, 022908 (2007).
- [30] W. Chen, Q.-Q. Sun, M. Xu, S.-J. Ding, D. W. Zhang, and L.-K. Wang, "Atomic layer deposition of hafnium oxide from tetrakis-(ethylmethylamino)-hafnium and water precursors", J. Phys. Chem. C 111, 6495 (2007).
- [31] W. Chen, M. Zhang, D. Zhang, S.-J. Ding, J.-J. Tan, M. Xu, X.-P. Qu, and L.-K. Wang, "Growth of high-density Ru- and RuO<sub>2</sub>-composite nanodots on atomic-layer-deposited Al<sub>2</sub>O<sub>3</sub> film", Appl. Surf. Sci. **253**, 4045 (2007).
- [32] S.-J. Ding, M. Zhang, W. Chen, D. W. Zhang, and L.-K. Wang, "Memory effect of metal-insulator-silicon capacitor with HfO<sub>2</sub>-Al<sub>2</sub>O<sub>3</sub> multilayer and hafnium nitride gate", J. Electron. Mater. **36**, 253 (2007).
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- [40] H.-L. Lu, W. Chen, S.-J. Ding, M. Xu, D. W. Zhang, and L.-K. Wang, "Quantum chemical study of adsorption and dissociation of H<sub>2</sub>S on the gallium-rich GaAs (001)-4×2 surface", J. Phys. Chem. B **110**, 9529 (2006).
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